	Hits	Search Text	DBs
1	69	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth$4 or cover$4 or thicken$5 or enhanc$4) same (coat$4 or layer or film)) and etch$4 and ((resist or photoresist) same pattern same (dimension or measurement or characteristic)) and (uniformity same (pattern or hole or via)) and (striation or unevenness)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	84	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth$4 or cover$4 or thicken$5 or enhanc$4) same (coat$4 or layer or film)) and etch$4 and ((resist or photoresist) same (dimension or measurement or characteristic)) and ((striation or roughness or variation or var$4) same (resist or photoresist) same (pattern or via or hole) same uneven$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	36	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth$4 or cover$4 or thicken$5 or enhanc$4) same (coat$4 or layer or film)) and etch$4 and ((resist or photoresist) same (dimension or measurement or characteristic)) and ((striation or roughness or variation or var$4) same (resist or photoresist) same (pattern or via or hole) same uneven$5) and uniformity	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB